2003



## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

S. Ohkawa et al.

Attorney Docket No.: SUSU121258

Application No.: 10/600,800

Group Art Unit: 2858

Filed:

June 19, 2003

Title:

SEMICONDUCTOR CHARACTERISTIC EVALUATION APPARATUS

### INFORMATION DISCLOSURE STATEMENT

Seattle, Washington 98101

December 4, 2003

#### TO THE COMMISSIONER FOR PATENTS:

Applicants are aware of the information listed in the attached form that may be material to the prosecution of the above-identified patent application.

- A copy of the listed publication is enclosed for the Examiner's use.
- $X_{-}$ 2. Pursuant to 37 C.F.R. § 1.97(b), this Information Disclosure Statement is being filed before the mailing date of a first Office Action on the merits.

Respectfully submitted,

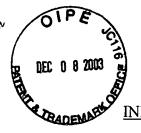
CHRISTENSEN O'CONNOR

Jeffrey M. Sakoi

Registration No. 32,059 Direct Dial No. 206.695.1713

I hereby certify that this correspondence is being deposited with the U.S. Postal Service in a sealed envelope as first class mail with postage thereon fully prepaid and addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on the below date.

hannon hih



# INFORMATION CITED BY APPLICANTS THAT MAY BE MATERIAL TO THE PROSECUTION OF THE SUBJECT APPLICATION

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$\Delta P$	plicants:

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## OTHER INFORMATION

(Including Author, Title, Date, Pertinent Pages, Etc.)

*Examiner Initial	Cite No.	
	O1	Chen, J.C., et al., "An On-Chip, Interconnect Capacitance Characterization Method With Sub-Femto-Farad Resolution," <i>Proceedings of the IEEE, International Conference on Microelectronic Test Structures</i> , Monterey, California, Vol. 10, March 1997, pp. 77-80.
Exan	niner	Date Considered

\*Examiner: Initial if reference considered, whether or not citation is in conformance with M.P.E.P. § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

JMS:snh